

ABSTRACT

A pellicle which can prevent the formation of foreign-matter deposits on a photo-mask during laser beam irradiation or storage and keep a high pattern accuracy for an extended period of time even when an exposure is made using a KrF or ArF excimer laser beam by removing deposit-causing materials from the pellicle itself in advance. During a pellicle producing process, a component member used or a completed product is heated or placed under pressure to thereby remove in advance substances produced from the component member used or the completed product.